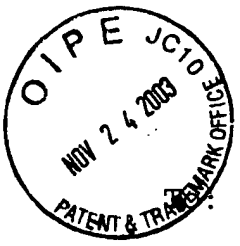
TSMC-01-999



November 18, 2003

To: Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572
28 Davis Avenue
Poughkeepsie, N.Y. 12603

Subject: Serial No. 10/650,601 08/28/03

Shih-Chi Lin

METHOD OF MANUFACTURING DIELECTRIC ISOLATED SILICON STRUCTURE

Grp. Art Unit:

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation In An Application.

The following Patents and/or Publications are submitted to comply with the duty of disclosure under CFR 1.97-1.99 and 37 CFR 1.56. Copies of each document is included herewith.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on November 21, 2003.

Stephen B. Ackerman, Reg.# 37761

Signature/Date 11/21/03

U.S. Patent 5,091,330 to Cambou et al., "Method of Fabricating a Dielectric Isolated Area," describes a method of fabricating a dielectric isolated area.

U.S. Patent 5,466,631 to Ichikawa et al., "Method for Producing Semiconductor Articles," describes a method for producing a semiconductor article.

U.S. Patent 5,773,352 to Hamajima, "Fabrication Process of Bonded Total Dielectric Isolation Substrate," describes a fabrication process of bonded total dielectric isolation substrate.

U.S. Patent 5,950,094 to Lin et al., "Method for Fabricating Fully Dielectric Isolated Silicon (FDIS)," describes a method for fabricating dielectric isolated silicon.

Sincerely,

Stephen B. Ackerman,
Reg. No. 37761

Form PTO-1449

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(Use several sheets if necessary)

Docket Number (Optional)	Application Number
TSMC-01-999	10/650,601
Applicant: Shih-Chi Lin	
Filing Date: 08/28/03	Group Art Unit

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
	5091330	2/25/92	Cambou et al.	437	62	12/28/90
	5466631	11/14/95	Ichikawa et al.	437	62	2/23/95
	5773352	6/30/98	Hamajima	438	406	3/23/95
	5950094	9/7/99	Lin et al.	438	409	2/18/99

FOREIGN PATENT DOCUMENTS

	Document Number	Date	Country	Class	Subclass	Translation YES	Translation NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER	DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.